

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Examiner: Eugene Lee

Group Art Unit: 2815

#4 / Per Amtd. A  
9.28.01  
R. Stiles

In re PATENT APPLICATION of

Applicants : Yao et al. )

Serial No. : N/A (parent application No.: )  
09/521,021 )

Filed : Herewith )

For : Alignment Mark )  
Configuration )

Atty Dkt : JCLA5662-CIP )

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents  
Washington, D.C. 20231

Dear Sir:

In response to the Office Action dated December 26, 2000 regarding the application No. 09/521,021 filed on March 8, 2000 and entitled "Alignment Mark Configuration". Applicant filed herewith a continuation-in-part (CIP) application thereof.

In the CIP application, the following amendments are made to the parent application No. 09/521,021:

On page 5, line 2, the following sentence is added: -- Preferably, the spacing "D" is from about 5d to 80d, more preferably, from about 5d to 50d. --.

Claim 1 is amended as follows:

1. An alignment mark configuration, which is applicable on a substrate comprising a plurality of layers, the alignment mark configuration comprising:
- an alignment mark on the substrate, wherein the alignment mark comprises a plurality of recesses and a spacing between the neighboring recesses is "d"; and